

4D Tracking Detectors: Monolithic Fast Timing Silicon Detectors

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Luminosity

- up to 10^{34}
- expect ~ 1 -2 interactions per event
 - Pileup should not be an issue, still need to identify primary vertex
- Bunch crossing ~ 10 ns
 - Fast readout or time stamp to identify bunch crossing for an event

Vertexing

- Hadron beam spot $\beta = 5$ cm

Particle identification

- time of flight
- dE/dx

Radiation damage

- Max 1×10^{15} 1 MeV n_{eq}/cm^2
 - Assuming $\sim 1\%$ of worst dose at HL-LHC
 - To be confirmed

Material Budget

- Keep as low as possible

Proposal:

4D Tracking Detectors: Monolithic Fast Timing Silicon Detectors

- Silicon already has small pixels (10-50 μm) for high spatial resolution
- Add timing resolution
 - better than bunch crossing
 - For vertex and track reconstruction
 - For particle ID
- MAPS may reduce cost and radiation length

Currently under investigation by Italian groups (INFN, Trento, Torino, ...), London, and UC Santa Cruz

5D Detector: x, y, z, time, energy

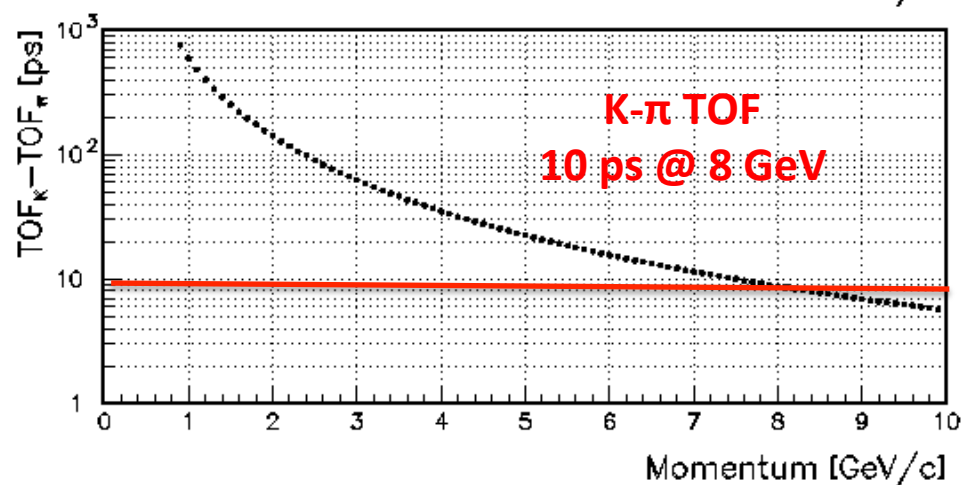
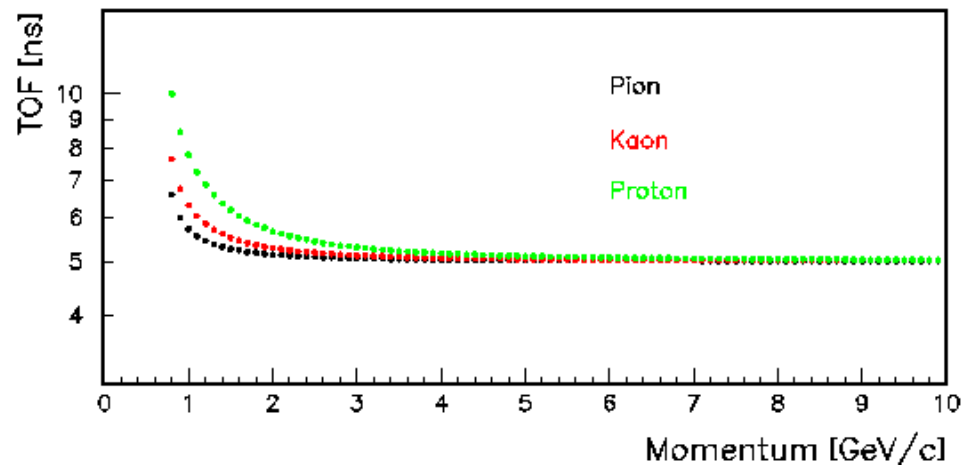
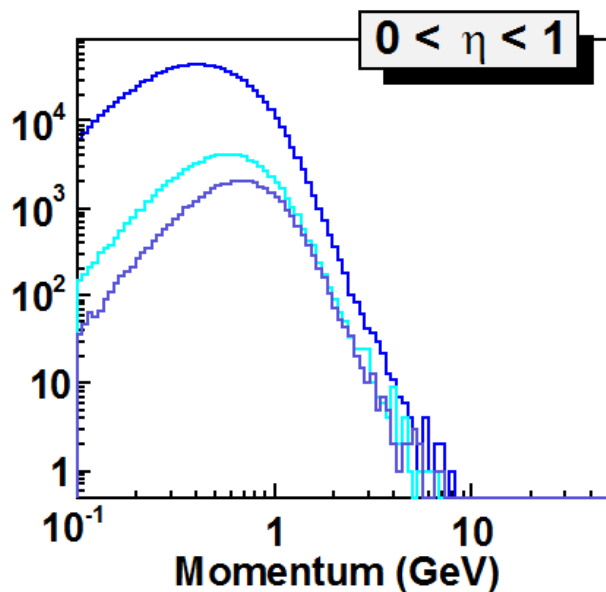
- Add as an option for an EM calorimeter

Never done before

Timing for Particle ID

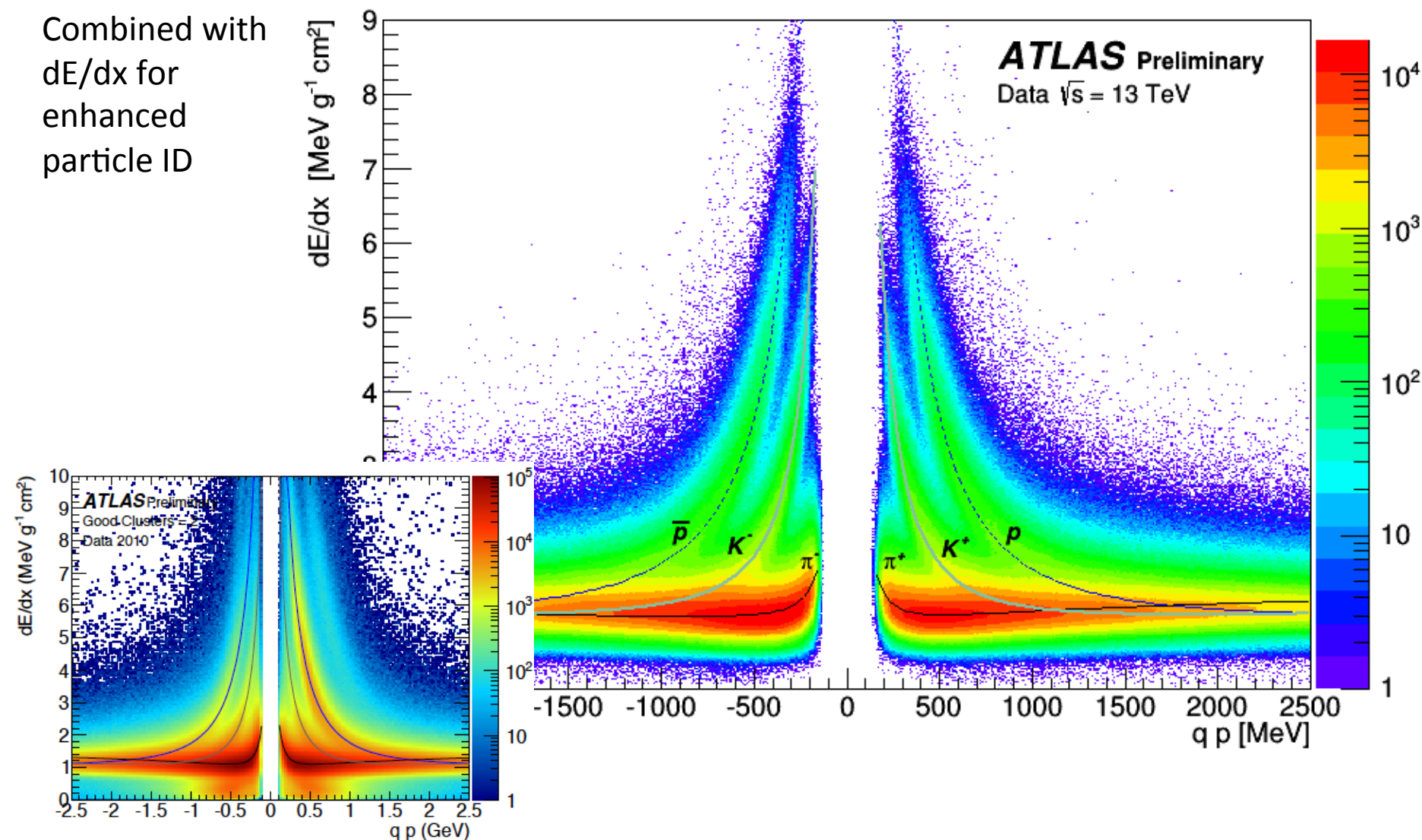
Particle ID:

- Expected energy range of charged particles is up to 10 GeV
- Using the time of flight, pion, kaon, and protons can be identified due to mass differences for a given momentum
- Kaon-pion separation requires resolutions on the order of 10 ps at 10 GeV



Timing for Particle ID

Particle ID:
Combined with
 dE/dx for
enhanced
particle ID

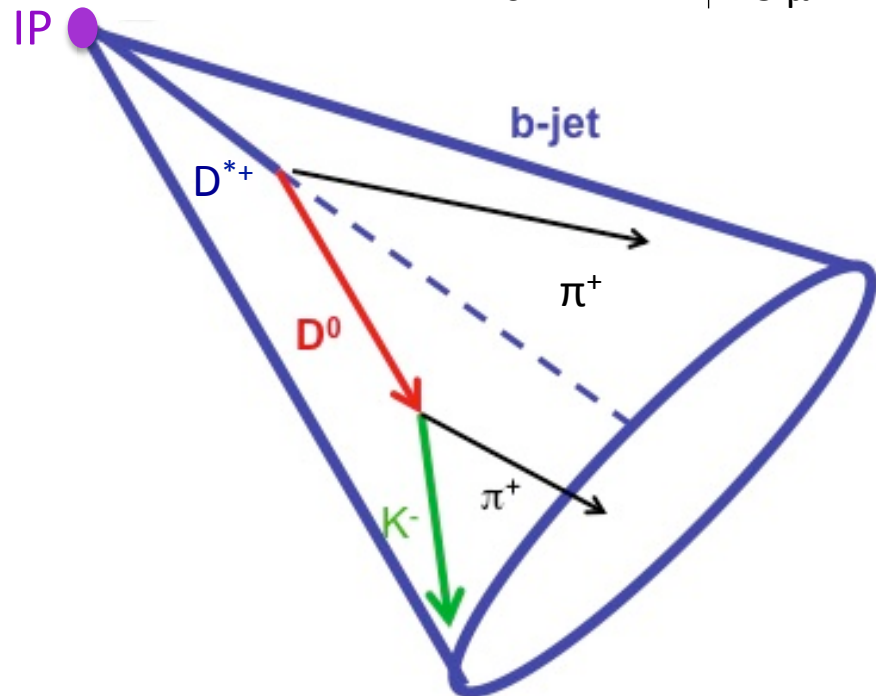
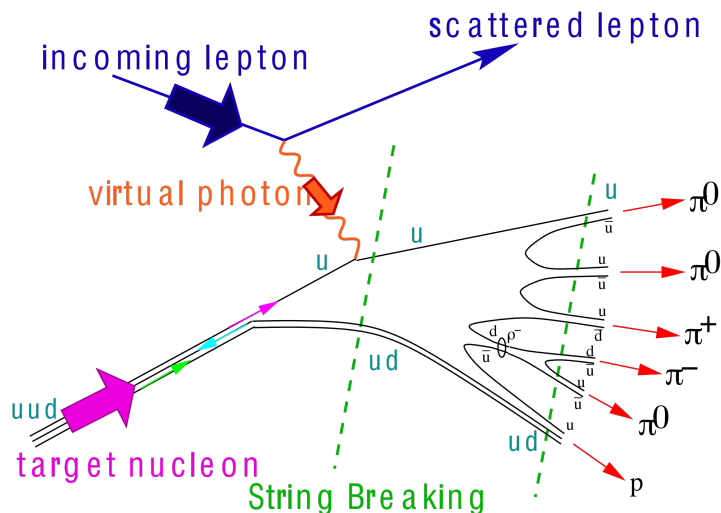


Timing for Track Reconstruction

Particles from the struck parton -> Jet substructure

- Identification of secondary/tertiary vertices
- Particle identification
- High resolution tracking
- Fragmentation function/structure function

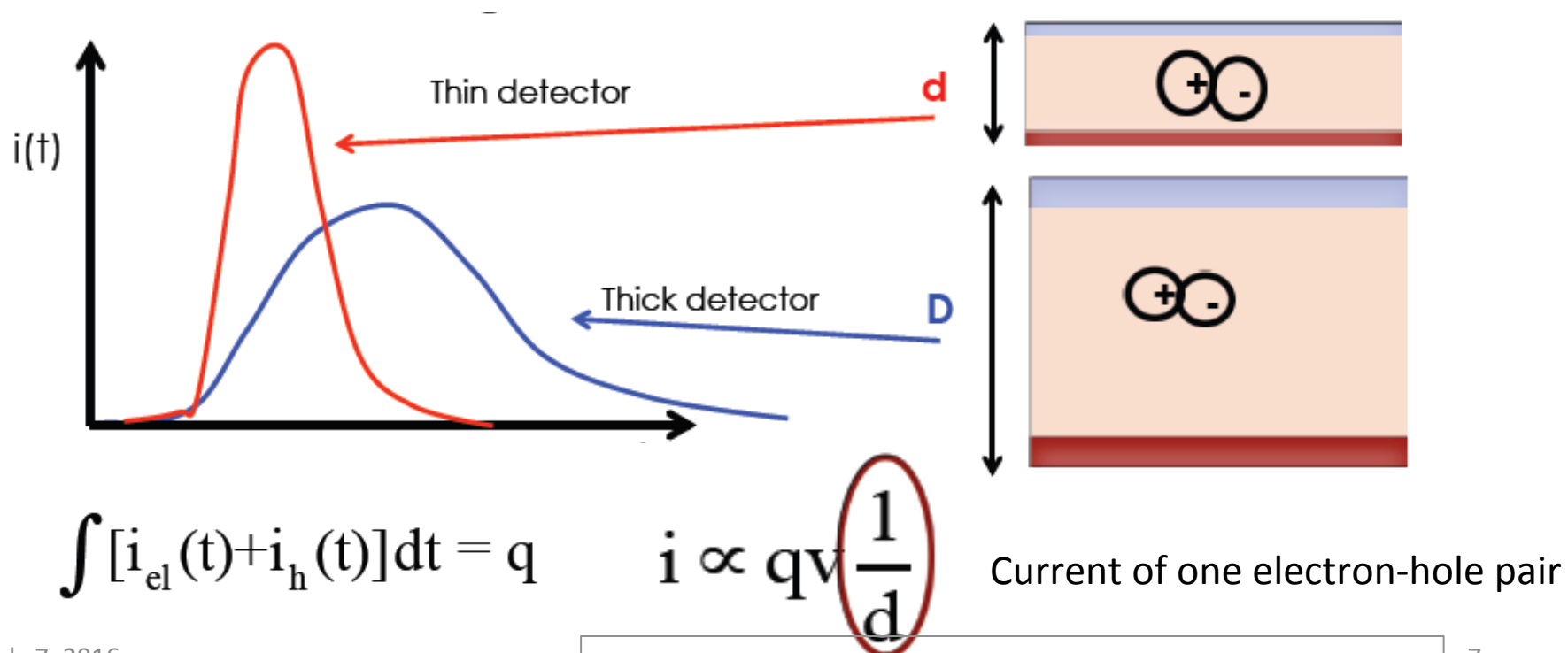
particle	$c\tau$
π^\pm	7.8 m
π^0	25 nm
K^\pm	3.7 m
K^0_S	2.7 cm
K^0_L	15.3 m
D^\pm	312 μm
D^0	123 μm



How do we achieve fast timing on the order of 10 ps?

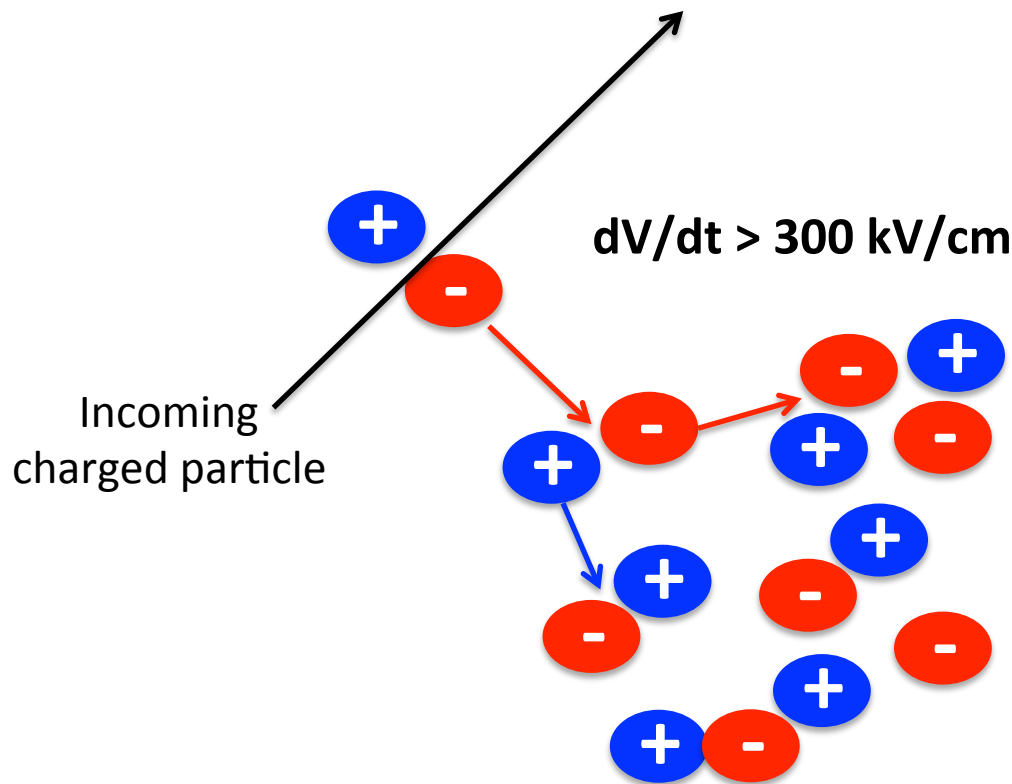
- Current traditional silicon technologies have rise time $\sim 1-10$ ns determined by the drift velocity in an electric field

1) Faster speeds achieved by reducing the length e-h pairs travel -> Thin Sensors



How do we achieve fast timing on the order of 10 ps?

2) Create an avalanche region to achieve larger gains



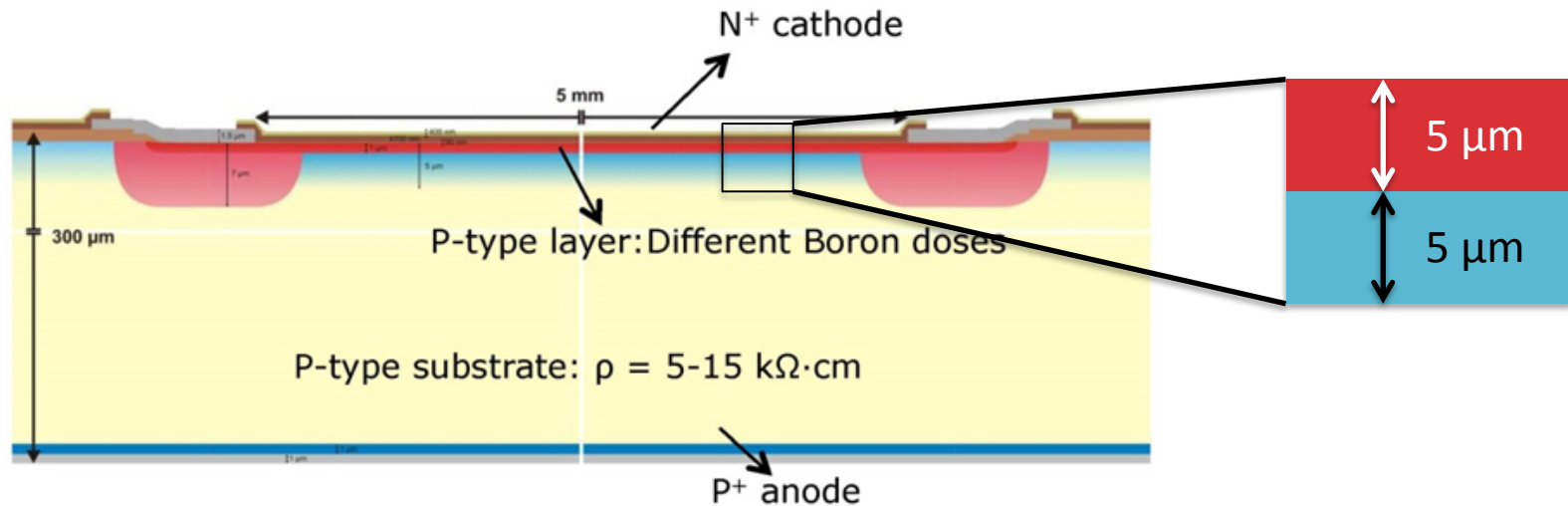
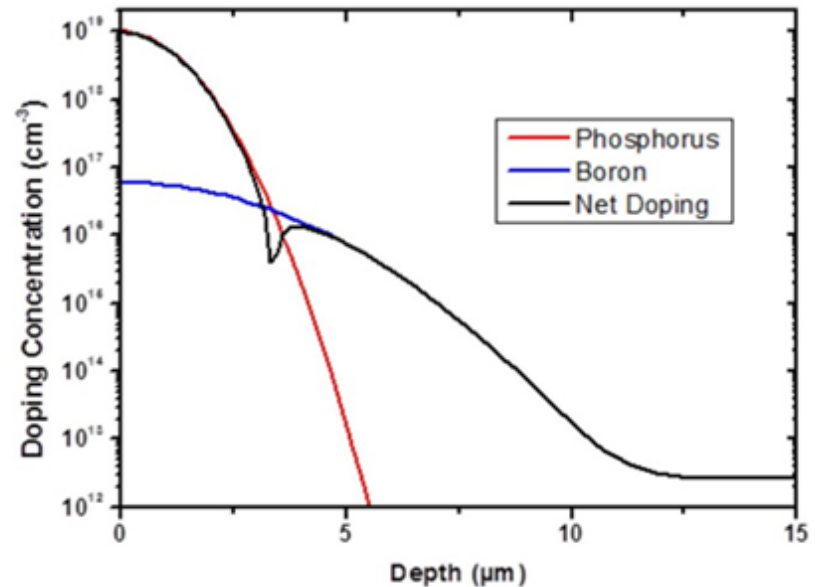
Create large potential gradient by applying a region of high doping concentration $N_D > 10^{16} / \text{cm}^3$

Gain factor $\sim >10\times$ more charge observed

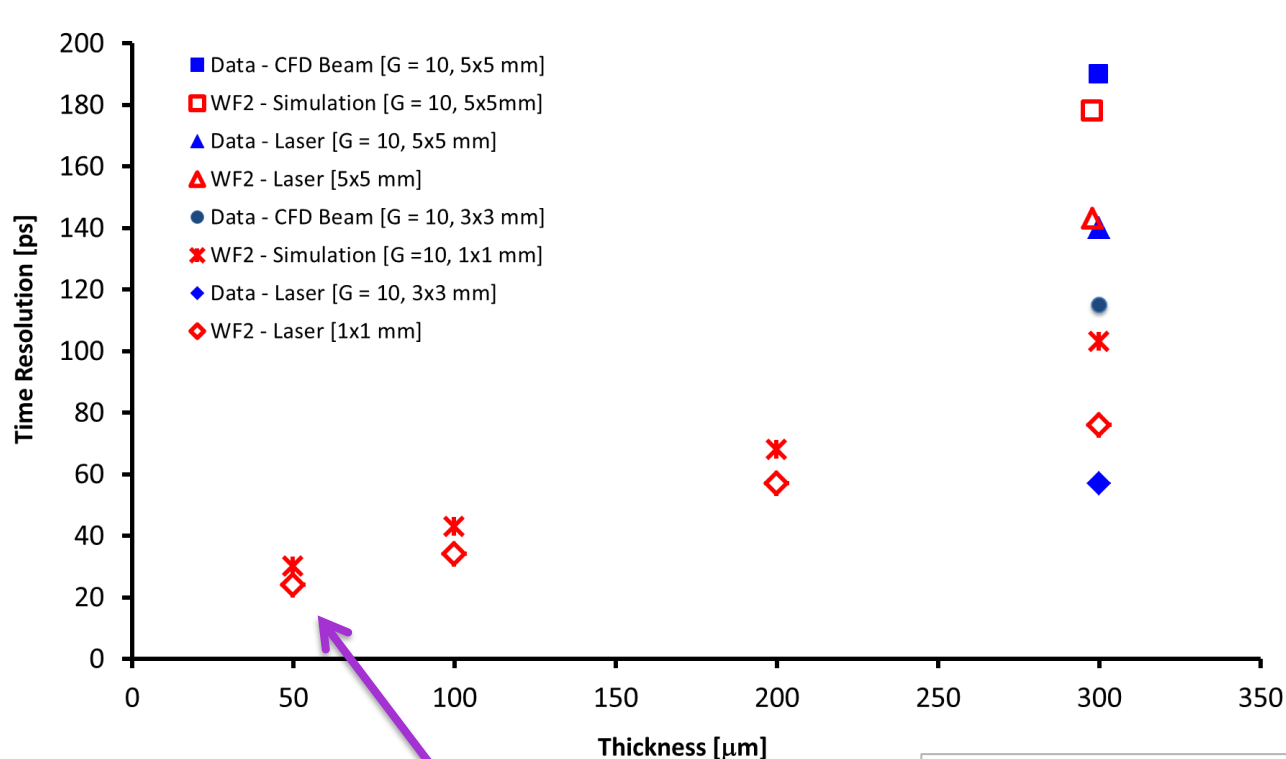
Low Gain Amplifying Detectors (LGAD)

LGAD

- amplification region, $\sim 5 \mu\text{m}$ thick
 - thin layer of Boron or Gallium
 - modifies the effective doping concentration profile \rightarrow electric field profile to create high field gradient
- Radiation tolerance shown up to $10^{14} n_{\text{eq}}/\text{cm}^2$
 - not as tolerant as traditional silicon due to the high reactivity of the accelerant layer



Silicon Detector R&D for EIC:



Sadrozinski, CPAD Meeting, Arlington 2015

Time resolution (in ideal lab conditions) approaching 10 ps

Limiting Factors:

Shot Noise

- Main factor is the leakage current in the bulk
- Multiplication region also adds to the noise due to stochastic nature
- Signal enhancement from gain increases more slowly (G) than the noise increase ($\sqrt{G^{2+x}}$) due to the gain factor limiting the overall effectiveness of increasing the gain on the S/N ratio -> limits gain factor, $G < 20$

Non-uniform field profile

- Reduces the amount of peak charge collected
- Distorts collected signal based on where incident particle strikes

- > Thin, square geometry electrodes and high resistivity bulk for uniform electric field profile
- > High field for maximal drift velocity
- > low capacitance to minimize noise
- > small volumes to minimize leakage current and Shot noise

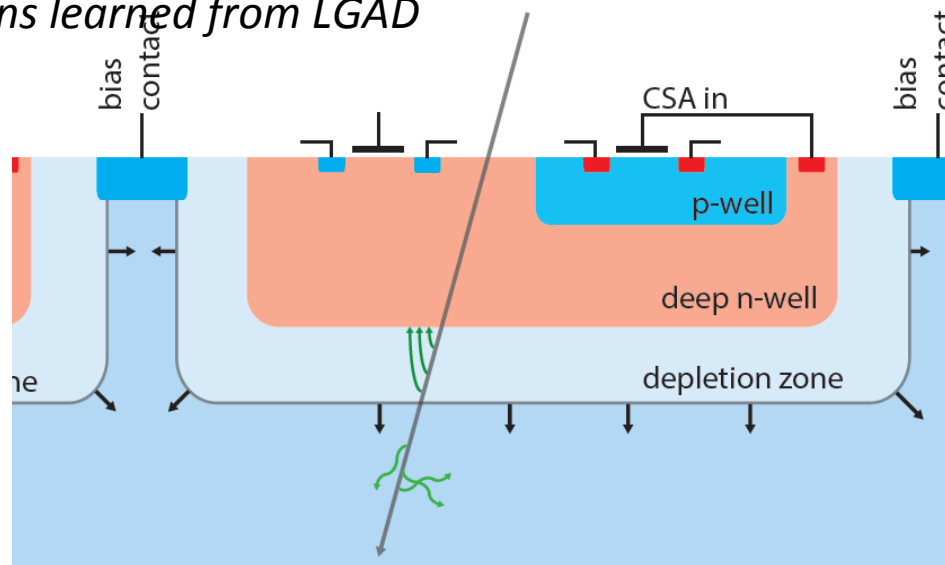
Answer: CMOS Monolithic Active Pixel Sensors (MAPS)

- Reduce effective capacitance -> noise
- Provide on-pixel amplification -> tolerate lower charge amplitude -> can go thinner

HVCMOS MAPS

(high voltage complimentary metal oxide semiconductor monolithic active pixel sensor)

- Less expensive by x2 than traditional silicon sensors
 - Integrated sensor + signal amplification
 - Use commercially available CMOS processing with a few modifications
 - Deep n-well to isolate on-pixel electronics
 - high resistivity substrates for high voltage without breakdown
- Timing is currently ~ 1 ns
 - *Apply gain layer in HV CMOS to achieve 10 ps timing? -> never done before*
 - *investigate the possibility with simulations*
 - *Can use lessons learned from LGAD*



4D Silicon Tracking Detector Design Targets

	Tracker	EM calorimeter	Best achieved
Pixel size	20-50 μm	1 cm	✓
Time resolution	10 ps	10-30 ps	50 ps
Radiation tolerance ($N_{\text{eq}}/\text{cm}^2$)	1×10^{15} (?)	1×10^{14}	1×10^{14}
Monolithic design	yes	yes	no

- Target values to be confirmed with simulations included in this proposal

Proposed Work: Year 1
Simulation intensive

1) Detector simulations

- Verify target requirements for timing, pixel size, radiation dose
- Investigate timing impacts on physics performance
 - Use the software framework for the SiD detector
 - Sergei Chekanov @ ANL is an expert and will supervise student/postdoc
 - Submitted separate proposal for (complimentary) simulation work
- Benefits of timing
 - Vertex reconstruction
 - Track reconstruction
 - Particle ID
 - As an EM calorimeter
 - In a forward detector

Proposed work: Year 1

2) Sensor Simulation

- Simulate the LGAD sensor using Sylvaco TCAD and/or WeightField2.0 (current software used for LGAD simulations)
 - Custom geometries
 - Specify different materials, non-uniformities
 - radiation effects
 - Response of an incident particle
 - Drift current generation
 - Diffusion current
 - Response to radiation damage
 - Electronics -> key to incorporate MAPS design
- Expertise at Argonne in the APS division
 - Agreed to share knowledge and Sylvaco license

Proposed work: Year 1

3) Sensor Design

- Identify challenges and methods to implement a MAPS design
 - Establish collaboration with a designer, TBD
 - Identify fabrication site that may be able to implement the parameters we need
 - CMOS process
 - High resistivity substrate
 - Doping for the gain layer

Proposed work: Year 1

3) LGAD Sensor Testing

- Collaborate with UC Santa Cruz to learn to test their devices
 - Set up DAQ chain, most likely SAMPPIX
 - Participate in test beams (travel funds)
 - Probe station measurements
 - IV, CV
 - Laser and/or radioactive source measurements to induce signal charge
 - Charge collection efficiency
 - Transient Current Technique for estimating the effective doping concentration
- Year 1 and 2: Establish procedures for microscopic analysis
 - Leverage experience in Material Science (and Nano Technology divisions)
 - Scanning laser microscopy
 - Spectroscopic techniques
 - Effective doping concentration, types of defects, trapping centers, resistivity, mobility, etc.
- Support to integrate LGAD to test stand and for MSD expertise is wrapped into the electrical engineer (EE) and mechanical engineer (ME) support at ~ 5 weeks each

Fast Timing Silicon Detectors

Plan Summary:

		PI	postdoc	grad student	EE	ME	Sensor designer	TCAD expert	Simulation expert	Material expert
	Year 1									
Detector Simulation	evaluate the impact of 4D detector on physics performance using fast/full simulation	✓		✓					✓	
	define target timing resolution	✓		✓					✓	
4D Sensor Simulation	TCAD simulation of monolithic LGAD device	✓	✓					✓		
4D Sensor Design	design 4D sensor concept for target timing resolution (expected 10-30 ps)	✓	✓				✓	✓		
4D Sensor Testing	develop laboratory test stand	✓	✓	✓	✓	✓				✓
	gain experience with existing LGAD devices	✓	✓	✓						
	Year 2									
4D Sensor Design	implement design concept to target timing	✓	✓				✓			
4D Sensor Fabrication	join multi-project wafer run for production	✓	✓				✓			
4D Sensor Testing	laboratory test stand characterization measurements	✓		✓	✓	✓				✓
	Year 3									
4D Sensor Testing	irradiate and test 4D sensor samples	✓	✓	✓	✓	✓				
	perform test beam measurements with the 4D sensors	✓	✓	✓	✓	✓				
4D Benchmarks	assess potential of the technology to meet design targets for EIC	✓	✓	✓						
	define main technological challenges	✓	✓	✓						
	propose solutions	✓	✓	✓						
4D Sensor Design (Optional)	implement solutions in new design	✓	✓							

Fast Timing Silicon Detectors

Budget

- All items represent fully loaded cost

	Cost (\$k):		
	Year 1	Year 2	Year 3
postdoc (50%)	65	65	65
graduate student	20	20	20
electrical engineer	20	10	10
mechanical engineer	20	10	10
sensor design	10	50	
multi-project wafer run		50	
materials and supplies	20	10	20
travel	5	5	15
TOTAL	160	220	140

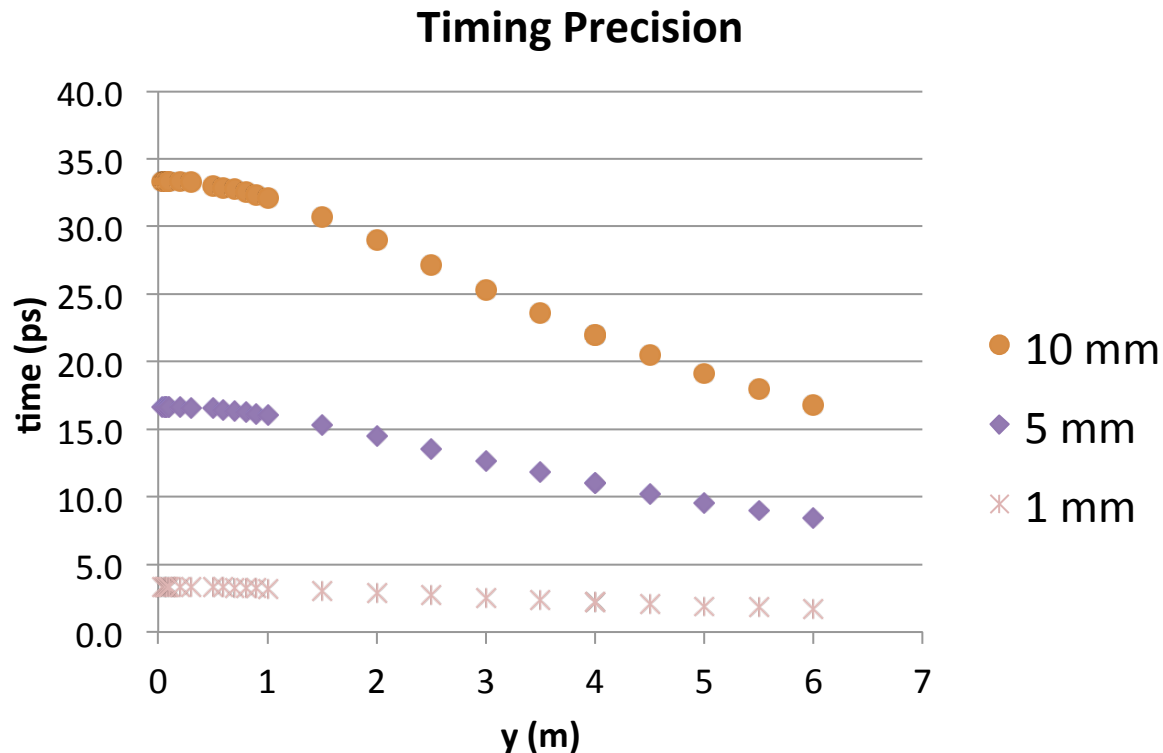
Summary:

- 4D detectors are a novel, but growing, area in silicon detectors
- Ambitious program to use fast timing silicon detectors in the EIC
- Now is the time to explore technological advances
- Proposal aims to determine whether Ultra Fast Silicon Detectors are worth investing in for the EIC
 - Clearly identify design targets
 - Establish the physics benefit from timing info
 - Simulate current LGAD sensors
 - Draw a roadmap toward Ultra Fast Silicon MAPS

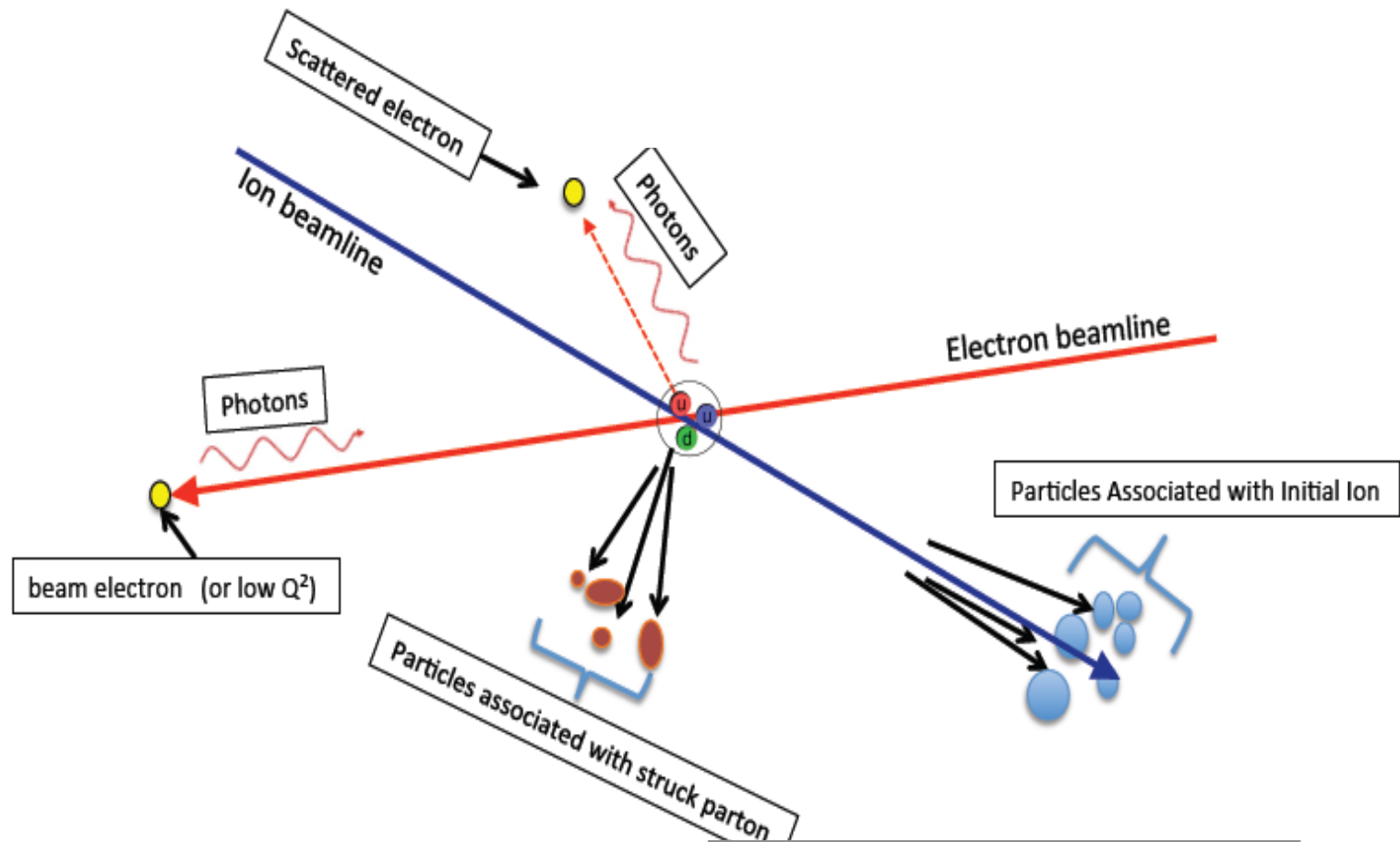
Thank You

Timing precision

- Vertex identification in forward regions with timing is possible
 - Time of flight to detector to identify vertex
- Example for a detector at 3.5 m in z from IP



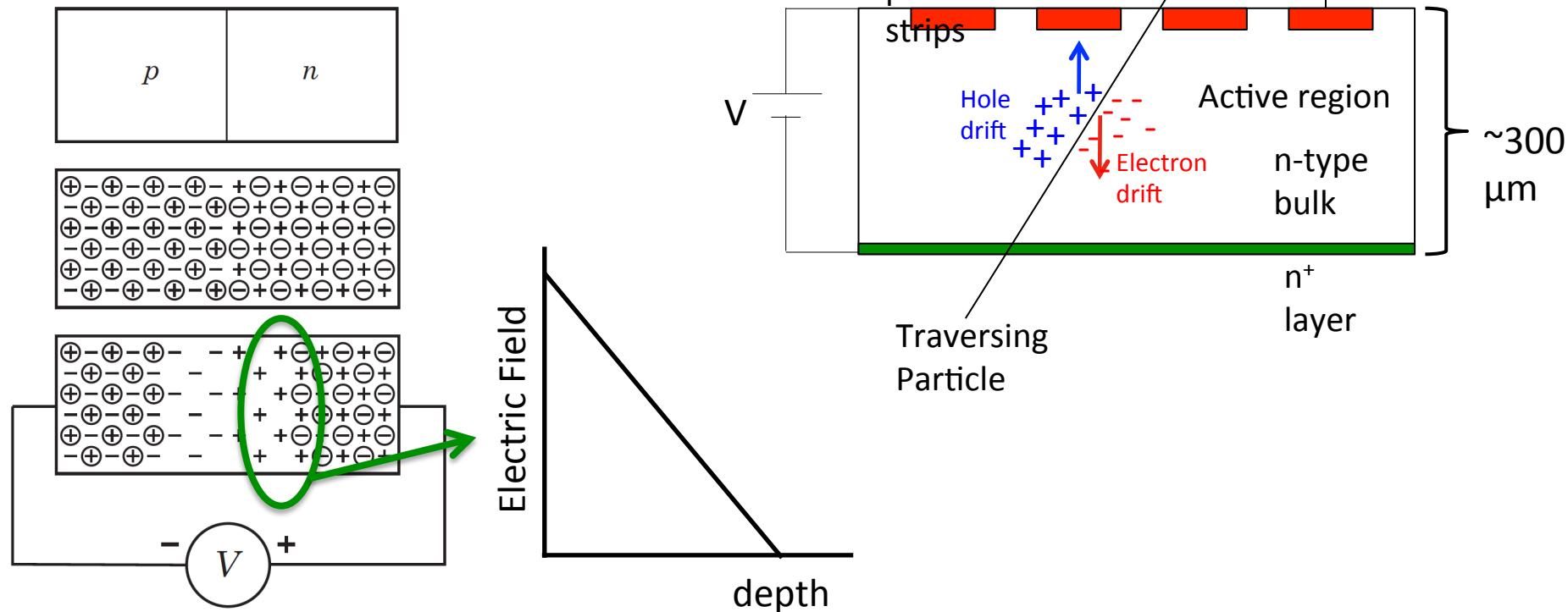
=> Timing on the order of 10 ps for particle ID, vertexing, and tracking

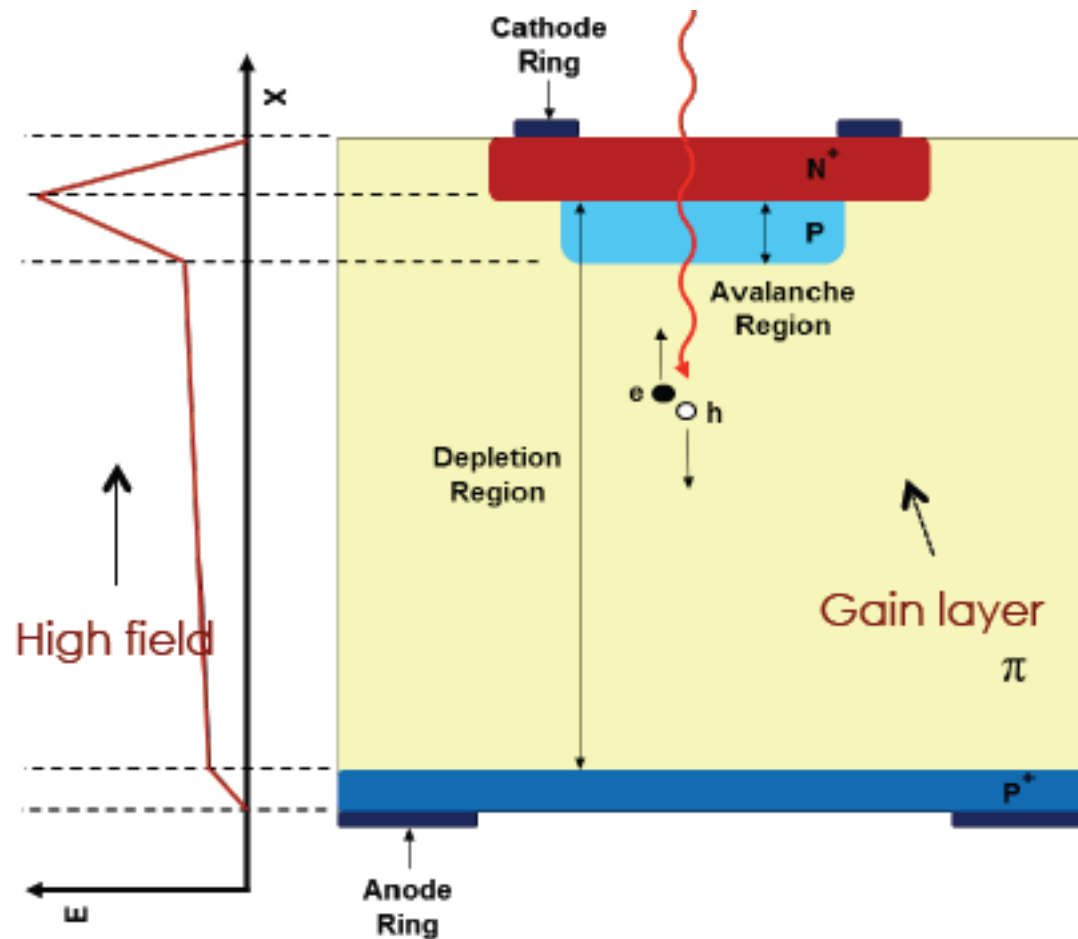


From Rik Yoshida's talk yesterday

Reminder of Silicon Detector Operation:

- Diode with p-n junction
- Apply bias voltage to create a region of stable space charge and linear electric field
 - this region is the depletion region or active area of the sensor
- MIP particle creates electron hole pairs
 - drift to strip implants and backplane
 - signal is read out by Front-End electronics

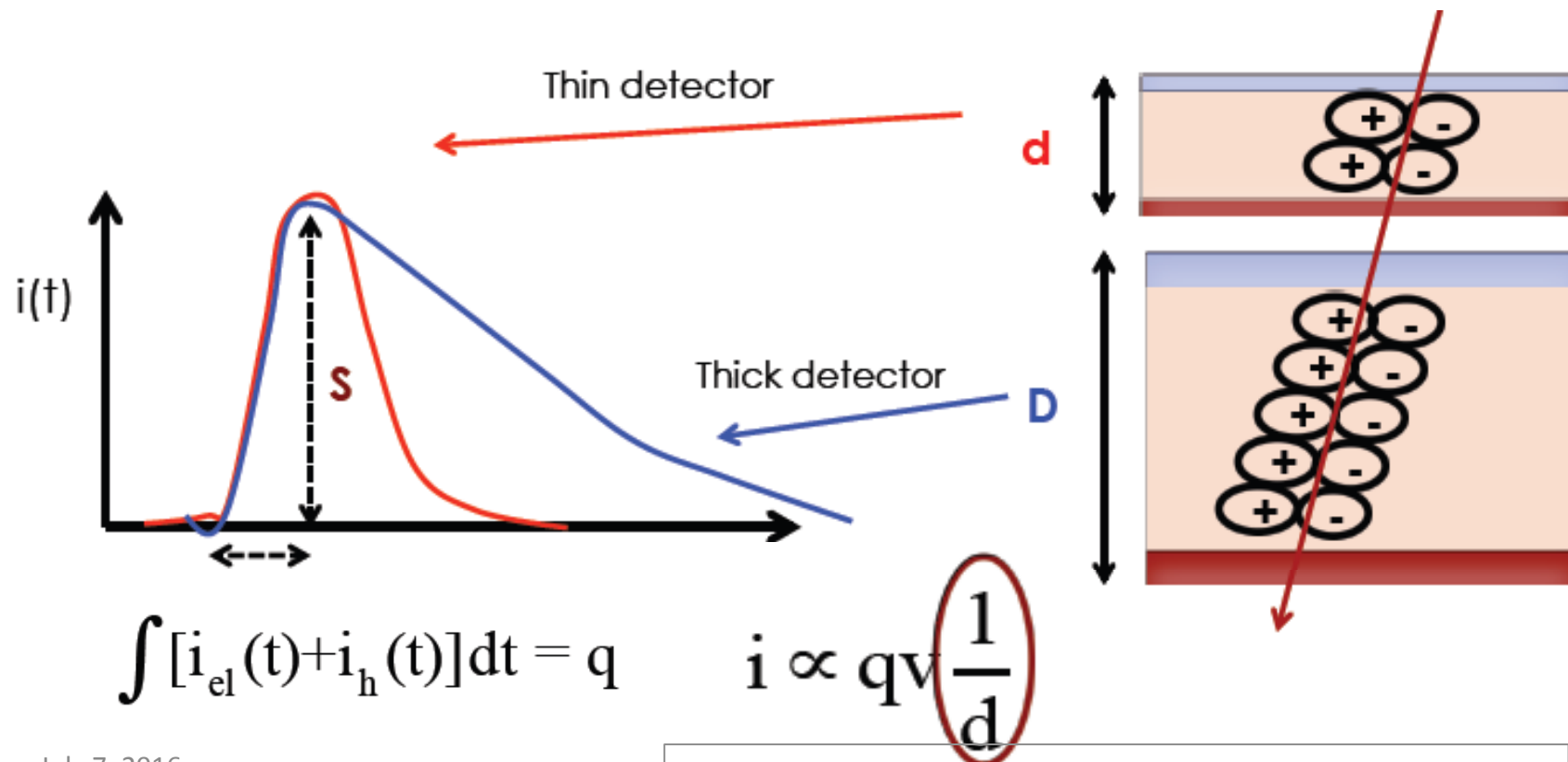




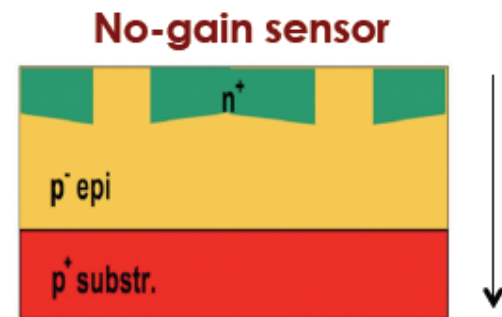
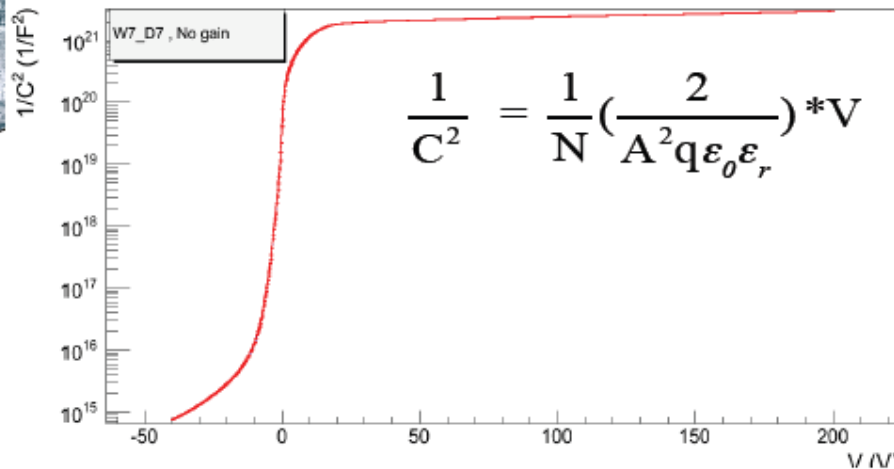
Nicolo Cartiglia CERN EP Detector Seminar 9/26/2014

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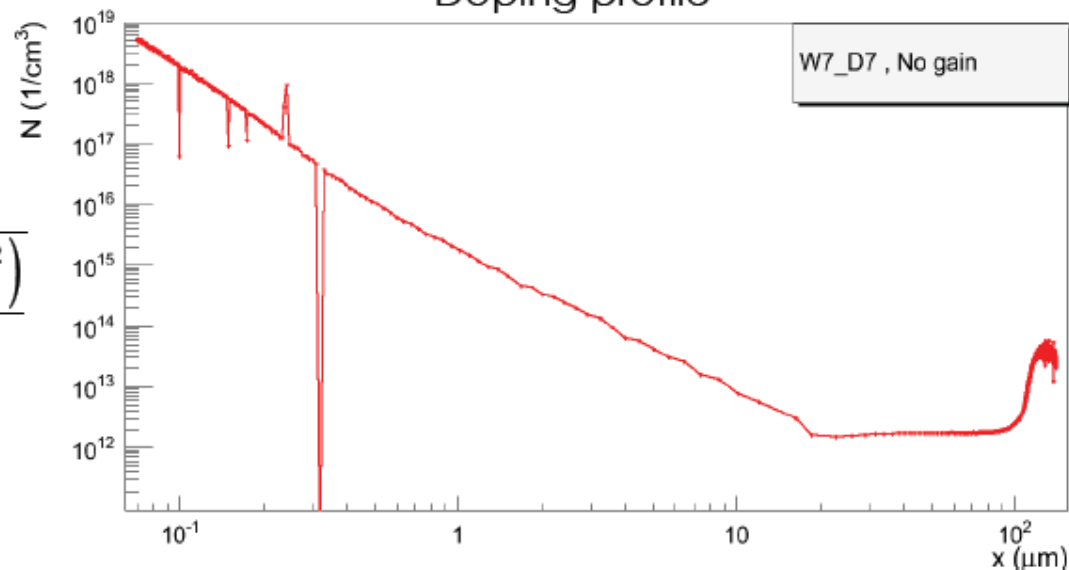
Doping profile from CV measurement - I



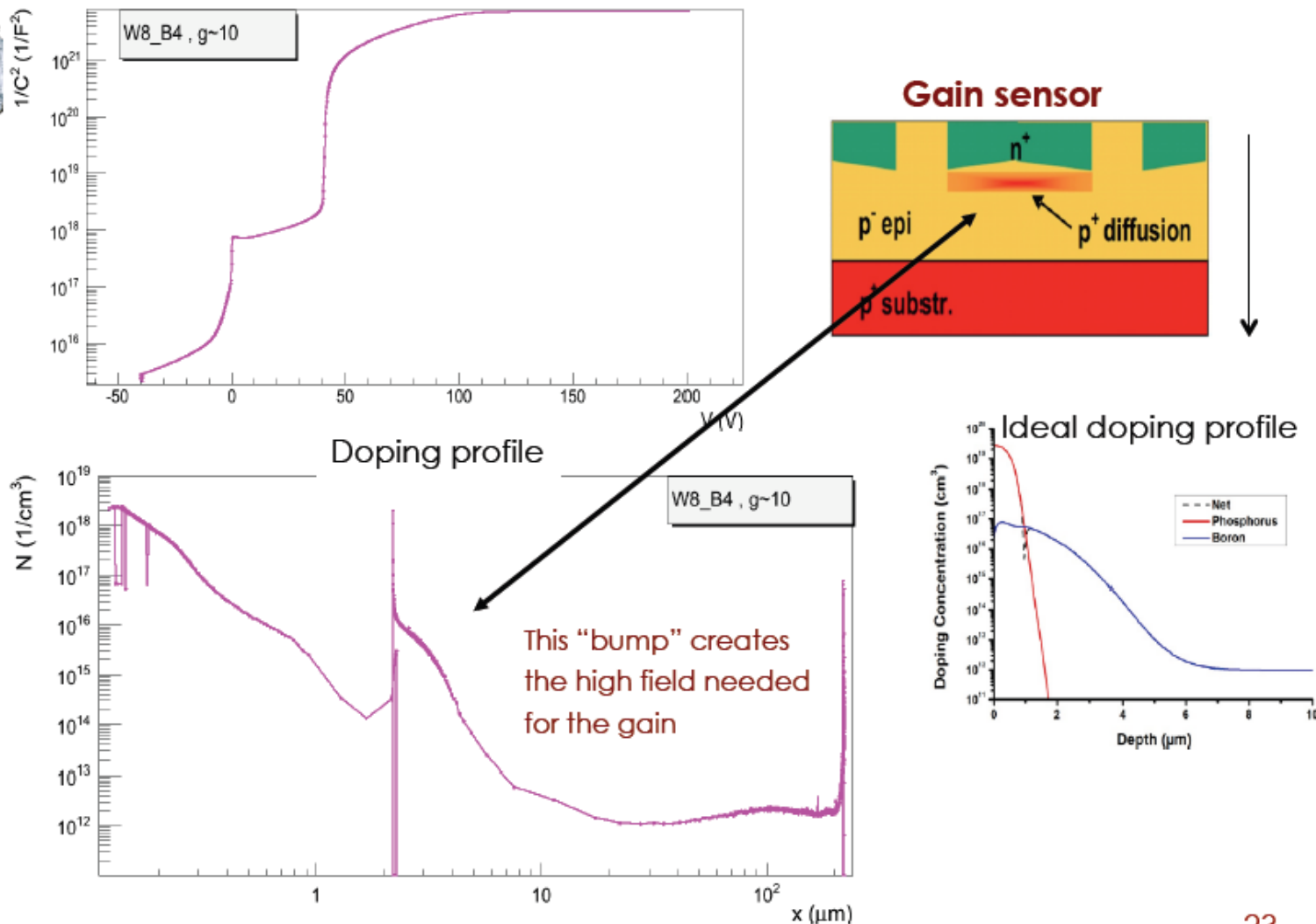
Doping profile

$$N = \frac{2}{q \epsilon_0 \epsilon_r A^2 \frac{d(1/C^2)}{dV}}$$

Doping



Doping profile from CV measurement - II

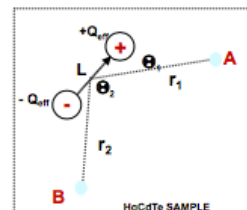




SPATIALLY RESOLVED CHARACTERIZATION OF HgCdTe MATERIALS AND DEVICES BY SCANNING LASER MICROSCOPY

-Non-destructive testing at various stages of device processing.
-Distribution and identification of electrically active defects
(inclusions, strain, damage, twin bound., bandgap and doping variations, dislocation clusters, precipitates, stacking faults)

Laser beam induced current (LBIC) mode

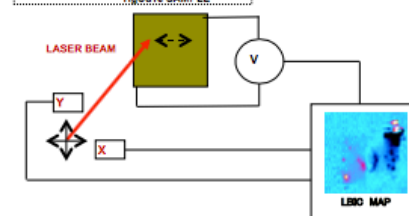


Electron-hole pairs generated at the point of illumination are separated by the built-in electrical field of regions in the vicinity of the incident light.

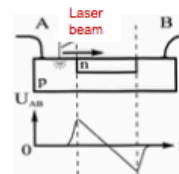
Voltage between points A and B

$$V_{AB} = \phi(r_1) - \phi(r_2) = Q_{eff} L / 2\pi\epsilon_0 (\cos\theta_1/r_1 - \cos\theta_2/r_2)$$

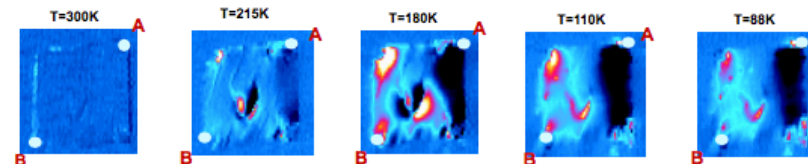
$+/- Q_{eff}$ - total charges of separated electron-hole pairs



Spatial distribution of LBIC for p-n junction



TEMPERATURE DEPENDENCE OF LBIC for MCT epitaxial film



Different electrically active areas of the film can be found with temperature LBIC measurements

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